

ABSTRACT

A pattern enlarged from a transfer pattern is divided into patterns (P_i) of a plurality of master reticles (R_i). Images of the patterns (P_i) of the plurality of master reticles (R_i) reduced by a projection optical system are successively projected and exposed on the surface of a blank (mask substrate) while stitching. Marks ($M1$, $M2$) indicating identification information for identifying a master reticle from another master reticle, transfer positions, etc. are formed on the master reticles (R_i). These marks ($M1$, $M2$) are detected before the exposure and exposure is performed in accordance with the information on the transfer position etc. shown by the marks ($M1$, $M2$) or reticle information (exposure conditions, various correction values, etc.) relating to the master reticles stored and held in advance corresponding to the identification information. The number of work steps when producing a working reticle using the plurality of master reticles is reduced and occurrence of work errors can be prevented.